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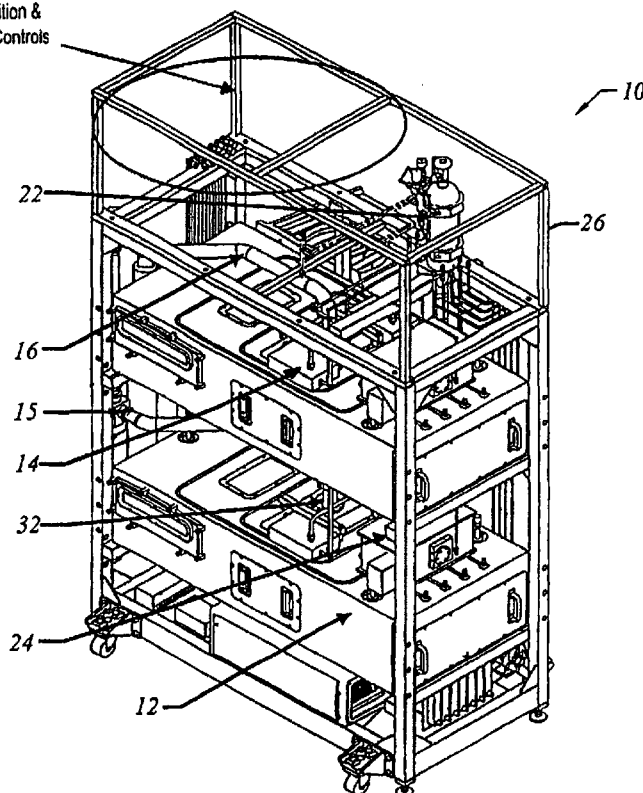
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(54) Title: METHOD AND SYSTEM FOR *IN SITU* CLEANING OF SEMICONDUCTOR MANUFACTURING EQUIPMENT USING COMBINATION CHEMISTRIES

Area for Deposition &
Cleaning Gas-Controls



(57) Abstract: An in situ, two step or combination, method and system for cleaning of semiconductor manufacturing equipment (10) is provided. The present invention utilizes two separate fluorine based chemistries in each step which selectively target the removal of different types of deposits that build up on the equipment surfaces. In particular, powdery and dense film-like solid deposits, as well as a combination of both, build up on the chamber (12) surfaces and associated equipment components. These two types of deposits are removed selectively by the present invention. Such selective targeting of combined cleaning steps, yields an improved cleaning technique. In another embodiment, the method and system of the present invention provides for cleaning of the chamber (12) and associated equipment using separate steps with different chemicals, and then performing these steps in a variety of desired sequences.



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